



Proceedings of the
Second International Workshop on
Visual Formalisms for Patterns
(VFfP 2010)

Preface

2 pages

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These proceedings contain selected and extended papers presented at VFfP'10, the second International Workshop on Visual Formalisms for Patterns. The workshop was held as a satellite event of the 2010 IEEE Symposium on Visual Languages and Human-Centric Computing, VL/HCC 2010 at Madrid. This series of workshops brings together researchers interested in the definition, usage and analysis of patterns through visual formalisms, which couple the simplicity of traditional methods for pattern expression with solid foundations for pattern-based activities.

Patterns are used in different disciplines as a way to record expert knowledge for problem solving in specific areas. In Software Engineering, they are increasingly used for the definition of software applications and frameworks, as well as in Model-Driven Engineering, to indicate parts of required architectures, drive code refactorings, or build model-to-model transformations. Their systematic use promotes quality, standardization, reusability and maintainability of software artefacts. The full realisation of their power is however hindered by the lack of a standard formalization of the notion of pattern. Presentations of patterns are typically given through natural language to explain their motivation, context and consequences; programming code to show usages of the pattern; and diagrams to communicate their structure and behaviour.

Several researchers have indicated the limitations of the current semi-formal devices for pattern definition – generally based on domain modelling languages, such as UML for design patterns, or Coloured Petri Nets for workflow – and research is active to propose rigorous formalisms, methodologies and languages for pattern definition in specific domains, as well as to propose general models of patterns.

The availability of formalisms will make common practices involving patterns, such as pattern discovery, pattern enforcement, pattern-based refactoring, etc., simpler and amenable to automation, and open new perspectives for pattern composition and analysis of pattern consequences. This workshop was conceived as a forum to communicate, discuss and advance in these directions.

The workshop technical contributions were carefully reviewed by three referees, and the program committee selected 7 long and 1 short papers, 6 of which were finally accepted for these post-proceedings. In addition, the technical programme included the keynote presentation “A formal approach to patterns in MDE” by Prof. Yngve Lamo, from the Bergen University College (Norway), also included in these post-proceedings. The workshop was organized in three technical sessions (“Architectural Patterns and Refactorings”, “Patterns for User Interfaces and Interaction Design” and “Specification Patterns”) and finished with a discussion panel on the benefits, limits and uses of pattern formalization.

We would like to thank the members of the Program Committee and the secondary reviewers for their excellent work – they are listed below – as well as the editorial team of ECEASST for their constant support.

April 2011.
Paolo Bottoni, Esther Guerra, Juan de Lara.
PC chairs of VFfP'10.



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